

**Retraction: “Growth of GaN nanowires on Si substrate using Ni catalyst in vertical chemical vapor deposition reactor”**  
**[Korean J. Chem. Eng., 21(1), 257 (2004)]**

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The authors hereby submit a formal retraction of the above article, because it was published in almost identical form in Journal of Crystal Growth, 257, pp97-103, 2003, previously published by us. The submission to the journal took place accidentally by the corresponding author without the knowledge of the co-authors. The correspond-

ing author deeply regrets the duplicate publication and any inconvenience of the co-authors, the editors, and the journal publisher, and others caused due to the publication of this article.

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**Retraction: “Growth mechanism of needle-shaped ZnO nanostructures over NiO-coated Si substrates”**  
**[Korean J. Chem. Eng., 21(3), 733 (2004)]**

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The authors hereby submit a formal retraction of the above article, because the data and the conclusion was published in a nearly identical article in Synthetic Metals, 144, pp61-68, 2004, previously published by us. The submission to the journal was made by the first author and the corresponding author without the knowledge of

other co-authors. The corresponding author deeply regrets the duplicate publication and any inconvenience of the co-authors, the editors, and the journal publisher, and others caused due to the publication of this article.

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